

ERRATA

Erratum: "Microstructural evolution and nanocrystal formation in Pb⁺-implanted ZrSiO₄ single crystals" [J. Appl. Phys. 94, 5695 (2003)]

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Figure 5(b). Labels are ordered incorrectly. The order, from the most intense to the less intense, should be as follows: $\alpha_i=0.2^\circ$, $\alpha_i=0.75^\circ$, $\alpha_i=1.5^\circ$, and $\alpha_i=5.0^\circ$.

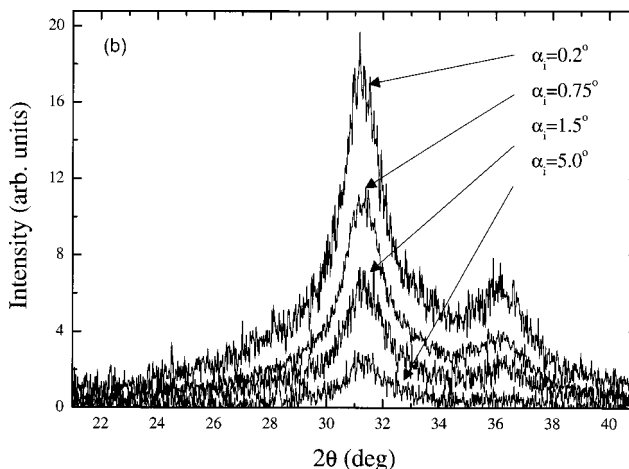


FIG. 5. (a) Intensity of the (111)/200 Pb peaks in the sample irradiated at 10^{17} Pb ions/cm² for an incident angle of 0.5° . Note the contribution due to the amorphous zircon layer. (b) Intensity of the (111)/200 Pb peaks as a function of the incident angle, α_i .